**INFORMATION DISCLOSURE CITATION**

(Use several sheets if necessary)

ATTY DOCKET NO.

ITL1054US(P17790)

SERIAL NO.

10/695,103

APPLICANT(S):

Huey-Chiang Liou et al.

FILING DATE:

October 28, 2003

GROUP ART UNIT:

2823

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

**FOREIGN PATENT DOCUMENTS**

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AJ							
	AK							
	AL							
	AM							
	AN							
	AO							
	AP							

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

T.D	AQ	S. Elhadj, J. W. Woody, V. S. Niu and R. F. Saraf, <i>Orientation of self-assembled block copolymer cylinders perpendicular to electric field in mesoscale film</i> , Applied Physics Letters, vol. 82, no. 6, 10 Feb. 2003, p. 871-3.
T.D	AR	Huiwen Liu, Bharat Bhushan, <i>Orientation and relocation of biphenyl thiol self-assembled monolayers under sliding</i> , Ultramicroscopy, vol. 91, no. 1-4, May 2002, p. 177-83.
T.D	AS	Sang Jung Ahn, Yun Kyeong Jang, Haeseong Lee, and Haiwon Lee, <i>Mechanism of atomic force microscopy anodization lithography on a mixed Langmuir-Blodgett resist of palmitic acid and hexadecylamine on silicon</i> , Applied Physics Letters, vol. 80, no. 14, 8 April 2002, p. 2592-4.
T.D	AT	Tiesheng Li, Masaya Mitsuishi, and Tokuji Miyashita, <i>Photodegradable polymer LB films for nano-lithographic imaging techniques</i> , Thin Solid Films, vol. 389, no. 1-2, 15 June 2001, p. 267-71.

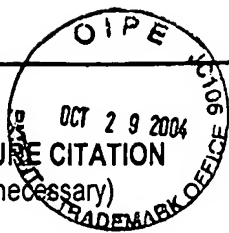
EXAMINE

T. DANG

DATE CONSIDERED

11/23/04

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



**INFORMATION DISCLOSURE CITATION**  
(Use several sheets if necessary)

ATTY DOCKET NO.  
ITL1054US(P17790)

SERIAL NO.  
10/695,103

APPLICANT(S):  
Huey-Chiang Liou et al.

FILING DATE:  
October 28, 2003

GROUP ART UNIT:  
2823

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

T.D	BA	N.G. Semaltianos, H. Araujo, and E.G. Wilson, <i>Polymerization of Langmuir-Blodgett films of diacetylenes</i> , Surface Science, vol. 460, no. 1-3, 20 July 2000, p. 182-9.
T.D	BB	Hiroyuki Sugimura, Atsushi Hozumi and Osamu Takai, <i>Fabrication of Coplanar Microstructures Composed of Multiple Organosilane Self-Assembled Monolayers</i> , IEICE Transactions on Electronics, vol. E83-C, no. 7, July 2000, p. 1099-103.
T.D	BC	M. Sundermann, J. Hartwich, K. Rott, D. Meyners, E. Majkova, U. Kleineberg, M. Grunze, U. Heinzmann, <i>Nanopatterning of Au absorber films on Mo/Si EUV multilayer mirrors by STM lithography in self-assembled monolayers</i> , Surface Science, vol. 454-456, 20 May 2000, p. 1104-9.
T.D	BD	Richard D. Peters, Xiao M. Yang, Tae K. Kim, B. H. Sohn, and Paul F. Nealey, <i>Using Self-Assembled Monolayers Exposed to X-rays To Control the Wetting Behavior of Thin Films of Diblock Copolymers</i> , Langmuir, vol.16, no.10, 16 May 2000, p. 4625-31.
T.D	BE	Hiroyuki Sugimura, Kazuya Ushiyama, Atsushi Hozumi, and Osamu Takai, <i>Micropatterning of Alkyl- and Fluoroalkylsilane Self-Assembled Monolayers Using Vacuum Ultraviolet Light</i> , Langmuir, vol. 16, no. 3, 8 Feb. 2000, p. 885-8.
T.D	BF	Hiroyuki Maruyama, Nobuyuki Kosai, Tadatake Sato, Shigehito Sagisaka, Hiroshi Segawa, Takeo Shimidzu and Kazuyoshi Tanaka, <i>Nanometer-Scale Lithography on the Oligosilane Langmuir-Blodgett Film</i> , Japanese Journal of Applied Physics, Part 1, vol. 36, no. 12A, Dec. 1997, p. 7312-16.
T.D	BG	Chang Nam Kim, Dong Woo Kang, Eung Ryul Kim, and Haiwon Lee, <i>Fabrication of a Polymethylphenylmethacrylate Resist by Using Electron Beam Lithography</i> , Journal of the Korean Physical Society, vol. 31, no. 1, July 1997, p. 154-7.
T.D	BH	T. Sato, and H. Ahmed, <i>Observation of a Coulomb staircase in electron transport through a molecularly linked chain of gold colloidal particles</i> , Applied Physics Letters, vol. 70, no. 20, 19 May 1997, p. 2759-61.
T.D	BI	Earl T. Ada, Luke Hanley, Sergei Etchin, John Melngailis, Walter J. Dressick, Mu-San Chen and Jeffrey M. Calvert, <i>Ion beam modification and patterning of organosilane self-assembled monolayers</i> , Journal of Vacuum Science & Technology B, vol. 13, no. 6, Nov.-Dec. 1995, p. 2189-96.
	BJ	
	BK	
	BL	
	BM	
	BN	
	BO	
	BP	
	BQ	

EXAMINER

T. DANG

DATE CONSIDERED

11/23/04

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.